

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 10-072594

(43)Date of publication of application : 17.03.1998

(51)Int.Cl.

C11D 7/26
B08B 3/08
C11D 7/32
C11D 7/34
C11D 7/36
H01L 21/304

(21)Application number : 09-152834

(71)Applicant : WAKO PURE CHEM IND LTD

(22)Date of filing : 27.05.1997

(72)Inventor : KAKIZAWA MASAHICO
ICHIKAWA OSAMU
HAYASHIDA KAZUYOSHI

(30)Priority

Priority number : 08165353 Priority date : 05.06.1996 Priority country : JP

(54) CLEANING AGENT

(57)Abstract:

PROBLEM TO BE SOLVED: To remove metallic impurities from the surface of a semiconductor substrate without corroding metal wiring and without detriment to the flatness of the surface by cleaning it with a cleaning agent prepd. by adding a complexing agent capable of forming a complex compd. with a metal-staining substance to an org. carboxylic acid.

SOLUTION: The org. acid has at least one carboxyl group, pref. 1-3 carboxyl groups, and may have 1-3 hydroxyl groups and/or 1-3 amino groups, a dicarboxylic or hydrocarboxylic acid being esp. pref. EDTA is an example of a complexing agent capable of forming a complex compd. with a substance which stains Al or Fe; however, a phosphonic acid compd. (e.g. 1-hydroxyethylidene-1,1'-diphosphonic acid) is an esp. pref. complexing agent. The amts. of the org. acid and the complexing agent compounded are 0.05-50wt.% and 0.01-10wt.%, respectively. Though the cleaning agent exhibits cleaning effects even at normal temp., it is heated to a suitable temp. when used since fine particles are removed more efficiently at higher temps. The cleaning agent can be compounded with many auxiliary ingredients.

LEGAL STATUS

[Date of request for examination] 16.06.1999

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number] 3219020

[Date of registration] 10.08.2001

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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